NOIDA INSTITUTE OF ENGINEERING AND TECHNOLOGY, GREATER NOIDA (An Autonomous Institute)



Affiliated to

DR. A.P.J. ABDUL KALAM TECHNICAL UNIVERSITY UTTAR PRADESH, LUCKNOW



Evaluation Scheme & Syllabus

For

Master of Technology in VLSI Design - First Year

(Effective from the Session: 2021-22)

NOIDA INSTITUTE OF ENGINEERING & TECHNOLOGY, GREATER NOIDA (An Autonomous Institute)

M. TECH (VLSI DESIGN)

Evaluation Scheme

SEMESTER I

SI.	Subject	Subject	Pe	eriod	ls	E	valuat	ion Schemes	5	Er Seme		Total	Credit
No.	Codes	J	L	Т	Р	СТ	ТА	TOTAL	PS	TE	PE		
1	AMTVL0101	CMOS Digital VLSI Design	3	0	0	20	10	30		70		100	3
2	AMTVL0102	Advanced Digital Design using Verilog	3	0	0	20	10	30		70		100	3
3	AMTCC0101	Research Process and Methodology	3	0	0	20	10	30		70		100	3
5		Elective -I*	3	0	0	20	10	30		70		100	3
6		Elective -II*	3	0	0	20	10	30		70		100	3
7	AMTVL0151	CMOS Digital VLSI Design Lab	0	0	4				20		30	50	2
8	AMTVL0152	Advanced Digital Design Lab using Verilog	0	0	4				20		30	50	2
		TOTAL			41			1. 4				600	19

(*) Refer the Electives list

Elective I*:

- 1. AMTVL0111 Microelectronics
- 2. AMTVL0112 MOS Device Modeling
- 3. AMTVL0113 Analog IC Design

Elective II*:

- 1. AMTVL0114 Microchip Fabrication Technology
- 2. AMTVL0115 Clean Room Technology and Maintenance
- 3. AMTVL0116 ULSI Technology

Abbreviation Used:-

L: Lecture, T: Tutorial, P: Practical, CT: Class Test, TA: Teacher Assessment, PS: Practical Sessional, TE: Theory End Semester Exam., PE: Practical End Semester Exam.

<u>NOIDA INSTITUTE OF ENGINEERING & TECHNOLOGY, GREATER NOIDA</u> (An Autonomous Institute)

M. TECH (VLSI DESIGN)

Evaluation Scheme SEMESTER II

SI.	Subject Subject		ł	Periods		Evaluation Schemes			End Semester		Total	Credit	
No	Codes	, v	L	Т	Р	СТ	ТА	TOTAL	PS	ТЕ	PE		
1	AMTVL0201	Digital Design Using FPGA and CPLD	3	0	0	20	10	30		70		100	3
2	AMTVL0202	Low Power VLSI Design	3	0	0	20	10	30		70		100	3
3		Elective –III*	3	0	0	20	10	30		70		100	3
4		Elective- IV*	3	0	0	20	10	30		70		100	3
5		Elective- V*	3	0	0	20	10	30		70		100	3
6	AMTVL0251	Digital Design Using FPGA and CPLD Lab	0	0	4				20		30	50	2
7	AMTVL0252	Low Power VLSI Design Lab	0	0	4				20		30	50	2
8	AMTVL0253	Seminar-I	0	0	2				50			50	1
		TOTAL										650	20

(*) Refer the Electives list

Elective III*:

- 1. AMTVL0211 VLSI Testing and Testability
- 2. AMTVL0212 VLSI DSP Architectures
- 3. AMTVL0213 Full Custom Design

Elective IV*:

- 1. AMTVL0214 MEMS Sensor Design
- 2. AMTVL0215 Nanoscale Devices: Modeling & Simulation
- 3. AMTVL0216 Physical Design & Automation

Elective V*:

- 1. AMTVL0217 Embedded Microcontrollers
- 2. AMTVL0218 Real Time Operating System
- 3. AMTVL0219 SOC Design using ARM

Abbreviation Used:-

L: Lecture, T: Tutorial, P: Practical, CT: Class Test, TA: Teacher Assessment, PS: Practical Sessional, TE: Theory End Semester Exam., PE: Practical End Semester Exam.

	M. TECH FIRST YEAR					
Course Code	AMTVL0101	LTP	Credit			
Course Title	CMOS Digital VLSI Design	300	03			
Course Object	tive:					
1	To explain basics of MOS switch, MOS fabrication and					
	their characteristics.					
2	To explain basic concept of CMOS inverter operation, its					
	characteristics and switching power dissipation.					
3	To design static CMOS combinational and sequential					
	logic at the transistor level, including mask layout.					
4 5	To explain the concept of dynamic logic circuits. To design functional units including ROMs, SRAMs, and					
5	DRAM.					
Pre-requisites	Basics of CMOS.					
	Course Contents / Syllabus					
UNIT-I	MOS TRANSISTOR BASIC	101	nours			
	Basic, MOS switch, VLSI Design flow & Y-Chart, Basic					
equation and sec	cond order effect, Fabrication Process Flow: Basic Steps, Design Rules, MOS inverters: DC transfer characteristics	The CM	OS n-Well			
capacitances.		, incentap,	1100121			
UNIT-II	CMOS INVERTER		9hours			
VIH, Vth, Desig Switching charac	Circuit operation, DC transfer characteristics, noise margin: n of CMOS inverter, Supply voltage scaling, power and teristic: Delay time definition, calculation of delay times, Switching Power dissipation of CMOS inverter. COMBINATIONAL & SEQUENTIAL MOS LOGIC	area cons	siderations.			
	CIRCUITS		onours			
circuits design – OIA gates, CMO Sequential MOS	Combinational MOS Logic Circuits: MOS logic circuits with NMOS loads, Complex Logic circuits design – Realizing Boolean expressions using NMOS gates and CMOS gates, AOI and OIA gates, CMOS full adder, CMOS transmission gates, Designing with Transmission gates, Sequential MOS Logic Circuits: Behavior of bi-stable elements, D latch, SR Latch, Clocked latch and flip flop circuits, CMOS, and edge triggered flip-flop.					
UNIT-IV	DYNAMIC LOGIC CIRCUITS		9hours			
Logic Circuits: H	Logic Circuits: Basic principle of pass transistor circuits, Voltage Bootstrapping, Synchronous dynamic circuit techniques, Dynamic CMOS transmission gate logic, High performance Dynamic					
UNIT-V	SEMICONDUCTOR MEMORIES		8 hours			
currents in DRAI	Iemories: Types, RAM array organization, DRAM – Types, M cell and refresh operation, SRAM operation Leakage curr IOR flash and NAND flash					
~ ~	me: After successful completion of this course students will l	be able to				
CO 1	To identify the fabrication process of CMOS transistor.					

CO 2	To identify basic concept of CMOS inverter operation, its	
	characteristics and switching power dissipation.	
CO 3	Design combinational & Sequential MOS logic circuits	
	like latches and flip flops.	
CO 4	Explain and design synchronous dynamic pass transistor	
	circuits	
CO 5	Analyse SRAM cell and memory arrays.	

Text Books

1. Sung-Mo Kang & Yusuf Leblebici, CMOS Digital Integrated Circuits - Analysis & Design, , MGH, Third Ed., 2003

2. Jan M Rabaey, Digital Integrated Circuits - A Design Perspective, Prentice Hall, Second Edition, 2005

3. David A. Hodges, Horace G. Jackson, and Resve A. Saleh, Analysis and Design of Digital Integrated Circuits, Third Edition, McGraw-Hill, 2004

Reference Books

1. R. J. Baker, H. W. Li, and D. E. Boyce, CMOS circuit design, layout, and simulation, Wiley-IEEE Press, 2007

2. Christopher Saint and Judy Saint, IC layout basics: A practical guide, McGraw-Hill Professional, 2001

	M. TECH FIRST YEAR				
Course Code	AMTVL0102	LTP	Credit		
Course Title	Advanced Digital Design using Verilog	300	03		
Course Object			1		
1	Study and explain the basic concepts Verilog HDI	L.			
2	Implement digital circuits using distinct design sty				
3	Design and synthesis digital circuits using HDLs.	·			
4 Study the concepts of data path design and switch level modeling.					
5	Explain about pipelining and processor design.				
Pre-requisites:	Digital System Design		•		
	Course Contents / Syllabus				
UNIT-I	INTRODUCTION TO HARDWARE DESC	RIPTION	8 hours		
	LANGUAGE (HDL)		0 11001 5		
Digital System D (HDL), Verilog D operators, Data ty	rdware description language (HDL), Verilog langua esign Process, Hardware modeling, Introduction to language features, elements of Verilog, Top-Dow pes in Verilog; net type, reg type, wire type, Veril delays and simulation, inertial delay effects and pu	o hardware vn, Bottom og Models	description language -up Design, Verilog of propagation delay		
UNIT-II	DISTINCT DESIGN STYLES	150 10 10 10	8 hours		
flow level, proce	on styles, behavioral and structural design style, Ve dural assignment, blocking / non-blocking assign a, writing Verilog test benches.				
UNIT-III	SYNTHESIS OF COMBINATIONAL & SEQUENTIAL LOGIC		8 hours		
	esis - technology-independent design, styles for synthesis of finite state machines, synthesis of gatures.				
UNIT-IV	DATA PATH AND CONTROLLER DESIGN		8 hours		
	tate machines, Data-path and Controller Design, S g register banks, Switch level modeling.	ynthesizab	e Verilog, Modeling		
UNIT-V	PIPELINING AND PROCESSOR DESIGN		8 hours		
Basic pipelining modeling of the p	concepts, Pipeline modeling, Pipeline implemen rocessor.	itation of a	a processor, Verilog		
Course Outcon to	me: After successful completion of this co	ourse stu	dents will be able		
CO 1	Outline the basic concepts Verilog HDL.				
CO 2	Design of digital circuits using distinct design styl	les.			
CO 3	Model HDL based Synthesis of digital circuits.				
CO 4	Analyze the concepts of data path design and swit modeling.	ch level			

CO 5	Implement pipelining and processor design using Verilog
	modeling.
Text books	
1. Navabi, Z., 199	9. Verilog digital system design. McGraw-Hill.
2. Palnitkar, S., 20	003. Verilog HDL: a guide to digital design and synthesis (Vol. 1). Prentice Hall
Professional.	
3. Arnold, M.G., 1	1998. Verilog digital computer design: Algorithms into hardware. Prentice-Hall,
Inc.	
Reference Boo	ks
1. Lin, M.B., 2008	3. Digital system designs and practices: using Verilog HDL and FPGAs. Wiley
Publishing.	
2. Unsalan, C. and	1 Tar, B., 2017. Digital system design with FPGA: implementation using Verilog
and VHDL. McGr	raw-H

Link:	
Unit 1	https://www.youtube.com/watch?v=wiNDn19GpRU&list=PLUtfVcb-iqn- EkuBs3arreilxa2UKIChl&index=3
Unit 2	https://www.youtube.com/watch?v=xWimKdisUXE&list=PLUtfVcb-iqn- EkuBs3arreilxa2UKIChl&index=12
Unit 3	https://www.youtube.com/watch?v=lpS3S2gVoB4&list=PLUtfVcb-iqn- EkuBs3arreilxa2UKIChl&index=23
Unit 4	https://www.youtube.com/watch?v=cIDoJtYdDVA&t=66s
Unit 5	https://www.youtube.com/watch?v=w1u338oIeTQ

Course Code	AMTCC0101	LTP Credit
Course Title	Research Process & Methodology	3 0 0 03
Course Obje	ctive:	
	o explain the concept / fundamentals of research	and their types
	o study the methods of research design and steps	
	o explain the methods of data collection and chniques	procedure of sampling
4 T	o analyze the data, apply the statistical technic oncept of hypothesis testing	ues and understand the
	o study the types of research report and technica	l writing.
	S: Basics of Statistics	
1	Course Contents / Syllab	ous
UNIT-I	INTRODUCTION TO RESEARCH	8 hours
Analytical, Ap	ctive and motivation of research, types and applied vs. Fundamental, Quantitative vs. Qua	litative, Conceptual vs. Empirica
	ds versus Methodology, significance of research	, criteria of good research.
	DESEADOU FODMULATION AND DES	
objective of Lit	RESEARCH FORMULATION AND DES as and steps involved, Definition and necessity erature review, Locating relevant literature, Rel	SIGN8 hoursof research problem. Importance ar ability of a source, Writing a surver
Research proce objective of Lit and identifying design.	as and steps involved, Definition and necessity erature review, Locating relevant literature, Rel the research problem, Literature Survey, Res	SIGN8 hoursof research problem. Importance ar ability of a source, Writing a surve earch Design , Methods of research
Research proce objective of Lit and identifying design. UNIT-III	as and steps involved, Definition and necessity erature review, Locating relevant literature, Rel the research problem, Literature Survey, Rese DATA COLLECTION	SIGN 8 hours of research problem. Importance ar ability of a source, Writing a surve earch Design , Methods of research 8 hours
Research proce objective of Lit and identifying design. UNIT-III Classification of primary and see	as and steps involved, Definition and necessity erature review, Locating relevant literature, Rel the research problem, Literature Survey, Res	SIGN8 hoursof research problem. Importance arability of a source, Writing a surveearch Design , Methods of research8 hourss of Data Collection, Collectionof Data Techniques, steps
Research proce objective of Lit and identifying design. UNIT-III Classification of primary and see	as and steps involved, Definition and necessity erature review, Locating relevant literature, Rel the research problem, Literature Survey, Rese DATA COLLECTION f Data, accepts of method validation, Method ondary data, sampling, need of sampling, samp	SIGN8 hoursof research problem. Importance arability of a source, Writing a surveearch Design , Methods of research8 hourss of Data Collection, Collectionof Data Techniques, steps
Research proce objective of Lit and identifying design. UNIT-III Classification of primary and see sampling design UNIT-IV Processing Ope appropriate stat statistical infer Visualization –	as and steps involved, Definition and necessity as and steps involved, Definition and necessity erature review, Locating relevant literature, Rel the research problem, Literature Survey, Res DATA COLLECTION f Data, accepts of method validation, Method ondary data, sampling, need of sampling, samp , different types of sample designs, ethical consi DATA ANALYSIS rations, Data analysis, Types of analysis, Statistical technique, Hypothesis Testing, Data prence, Chi-Square Test, Analysis of variand Monitoring Research Experiments ,hands-on with	SIGN 8 hours of research problem. Importance ar ability of a source, Writing a surve earch Design , Methods of research 8 hours Is of Data Collection, Collection oling theory and Techniques, steps derations in research. 8 hours tistical techniques and choosing a rocessing software (e.g. SPSS etc. ce(ANOVA) and covariance, Data
Research proce objective of Lit and identifying design. UNIT-III Classification of primary and see sampling design UNIT-IV Processing Ope appropriate star statistical infer Visualization – UNIT-V	and steps involved, Definition and necessity as and steps involved, Definition and necessity erature review, Locating relevant literature, Rel the research problem, Literature Survey, Res DATA COLLECTION f Data, accepts of method validation, Method ondary data, sampling, need of sampling, samp , different types of sample designs, ethical consi DATA ANALYSIS rations, Data analysis, Types of analysis, Sta istical technique, Hypothesis Testing, Data prence, Chi-Square Test, Analysis of variance	SIGN 8 hours of research problem. Importance are ability of a source, Writing a surver earch Design , Methods of research 8 hours ability of a source, Writing a surver earch Design , Methods of research 8 hours ability of Data Collection, Collection of the search 8 hours ability theory and Techniques, steps derations in research. 8 hours ability theory and Techniques, steps derations in research. 8 hours ability theory and Collection of the search. 8 hours black techniques and choosing a soccessing software (e.g. SPSS etc. se(ANOVA) and covariance, Data h LaTeX. NG OF RESEARCH

CO 1	Explain concept / fundamentals for different types of research				
CO 2	Apply relevant research Design technique				
CO 3	Use appropriate Data Collection technique				
CO 4	Evaluate statistical analysis which includes various parametric test and non-parametric test and ANOVA technique				
CO 5	Prepare research report and Publish ethically.				
Text books					
	othari, Gaurav Garg, Research Methodology Methods and Techniques, New Age onal publishers, Third Edition.				
	 Ranjit Kumar, Research Methodology: A Step-by-Step Guide for Beginners, 2nd Edition, SAGE 2005. 				
3. Deepak Chawla, NeenaSondhi, Research Methodology, Vikas Publication					
Reference Books					
1. Donald Co	oper & Pamela Schindler, Business Research Methods, TMGH, 9 th edition				
2 Creswell	John W. Research design: Qualitative, quantitative, and mixed methods approaches				

2. Creswell, John W. ,Research design: Qualitative, quantitative, and mixed methods approaches sage publications,2013

NPTEL/ You tube/ Faculty Video Link:

https://www.youtube.com/playlist?list=PL6G1C6j0WUTXqXL9O0CgTXCr1hL8HR2dY https://www.youtube.com/playlist?list=PLVok63jpnHrFFQI6BqkIksVqDnYG0ZI41 https://www.youtube.com/playlist?list=PLnbm2MNkZYwOVVedGBQtID-jKgj9dD8kW https://www.youtube.com/playlist?list=PLPjSqITyvDeWBBaFUbkLDJ0egyEYuNeR1 https://www.youtube.com/playlist?list=PLdj5pVg1kHiOypKNUmO0NKOfvoIThAv4N

		M. TECH FIRST YEAR		
Course C	ode	AMTVL0151	LTP	Credit
Course T	itle	CMOS Digital VLSI Design Lab	0 0 4	02
		List of Experiment		
Sr. No.	Nan	ne of Experiment		
1		y of Microwind software and its features.		
2	Desig	gn, simulate and verify the stick diagram of CMOS Inverter usi	ng Microw	vind.
3				
4				
5	Y=((gn, simulate and verify the operation of logic functio $(B+CD)(E+F)$)'		
6		gn, simulate and verify the operation of CMOS half adder using		
7	7 Design, simulate and verify the operation of CMOS full adder using two half adders in Microwind.			
8	Desig	gn, simulate and verify the operation of 4:1 Multiplexer in Micr	rowind.	
9		gn, simulate and verify the operation of logic function using I in Microwind: $Y = ((B+CD)(E+F))'$	Dynamic a	nd Domino
10	Desig	gn, simulate and verify pseudo NMOS Inverter.		
Lab Cou	rse O	utcome: After completion of this course students will be a	ble to	
CO 1	Anal	yze the features of Microwind software.		
CO 2	Desig	gn, simulate and verify the result of universal gates, XOR, XN	OR.	
CO 3		gn, simulate and verify the operation of logic function using Mi		
CO 4		gn, simulate and verify the operation of CMOS half/full adder u		owind.
CO 5	Desig	gn, simulate and verify the operation of Multiplexer in Microwi	ind.	
Link:				
-		utube.com/watch?v=F-8_caipPsY		
https://www	v.youti	ube.com/watch?v=S1VOEqApQvA		
https://wwv	v.youti	ube.com/watch?v=EHUJda2ttU8		
https://wwv	v.youti	ube.com/watch?v=yHJmFuexWbM		
https://wwv	v.youti	ube.com/watch?v=7K_0I6CjBOY		

	M. TECH FIRST YEAR				
Course Code	AMTVL0152	LTP	Credit		
Course Title	Advanced Digital Design Lab using Verilog	0 0 4	02		
-	d Functional Simulation of the following digital circuit elSim tools) using Verilog Hardware Description Lang		inx/		
Sr. No.	Name of Experiment				
1	Design and simulate the Verilog HDL code to describe Adder and Subtractor using three modeling styles.	the functio	ns of a Full		
2	 Design and simulate the Verilog HDL code for the following combinational circuits: a) 4x1 Multiplexer using gate level modeling 				
	 b) 8x1 Multiplexer using dataflow level mode c) 4-Bit Binary to Gray Code Converter using modeling 				
3	Design and simulate the Verilog HDL code for the follo circuit: a) 3 to 8 Decoder b) 8 to 3 Encoder	wing com	oinational		
4	Design and simulate the Verilog HDL code combinational circuits using structural modeling. a) 16x1 Multiplexer using 4x1 Mux b) 4- Bit Comparator using 1 Bit Comparato		following		
5	Design and simulate the Verilog HDL code for the b bitwise logical operations of ALU.		netic and		
6	Design and simulate the Verilog HDL code for the flip- a) SR FF b) JK FF c) D FF	-flops:			
7	 d) T FF Design and simulate the Verilog HDL code for the folloa) a) 4- Bit Up-Down Counter b) BCD counter (Synchronous reset and asyn 	-			
8	Design and simulate the Verilog HDL code for the f register: a) SISO b) SIPO c) PIPO d) PISO				
9	Design and simulate the Verilog HDL code for 4- Bit un	iversal shi	ft register.		
10	Design and simulate the Verilog HDL code to detect the		0		
Lab Course	Outcome: After completion of this course students an	<u> </u>			
CO 1	Translate the digital design into the Verilog HDL.				
CO 2	Design the combinational circuits in Verilog HDL.				
CO 3	Design the sequential circuits in Verilog HDL.				

CO 4	Implement different digital circuits with component testing.
Link:	
Unit 1	https://www.youtube.com/watch?v=wiNDn19GpRU&list=PLUtfVcb-iqn- EkuBs3arreilxa2UKIChl&index=3
Unit 2	https://www.youtube.com/watch?v=xWimKdisUXE&list=PLUtfVcb-iqn- EkuBs3arreilxa2UKIChl&index=12
Unit 3	https://www.youtube.com/watch?v=lpS3S2gVoB4&list=PLUtfVcb-iqn- EkuBs3arreilxa2UKIChl&index=23
Unit 4	https://www.youtube.com/watch?v=cIDoJtYdDVA&t=66s
Unit 5	https://www.youtube.com/watch?v=w1u338oIeTQ

		M. TECH FIRST YEAR		
Course C	ode	AMTVL0111	LTP	Credit
Course T	itle	Microelectronics	300	03
Course O	bjec	tive:		
		ovide the knowledge of different fabrication proc	esses like	e
		y, oxidation and their applications.		
	-	ovide the knowledge of diffusion, ion implantation and	different	
		of lithography and etching.		
		ovide the knowledge of Discrete devices and its fabricat		
	-	ovide the knowledge of Different digital logic circuits a	nd analog	
	circuit	s. by the basic knowledge of BiCMOS ICs and their pa	chaging	
			ckagilig.	
rre-requi	isites	Basics of digital electronics, CMOS designing.		
		Course Contents / Syllabus FABRICATION PROCESS	01	
UNIT-I	•			ours
		axy, Vapour phase epitaxy, Liquid phase epitaxy a	nd Molec	ular-Bean
		n on insulators. Polyviliaan Film Danasitian, Tharmal avidation, Diala	othic and	Dolumiliaar
		Polysilicon Film Deposition: Thermal oxidation, Diele- etallization & it's Application, Masking.	curic and I	Polysincol
UNIT-II	511, 1 VI	DIFFUSION & ION IMPLANTATION		8 hours
	ffusio	n, Distribution and range of implanted ions, Annealin	ng and ag	
dopants.		ii, Distribution and range of implanted ions, Anneam	ing and ac	
-		HY & ETCHING: Optical lithography, X-ray lithograp	ohv. Ion li	thography
		lithography, Wet chemical etching and Dry chemical et		
UNIT-III		DISCRETE DEVICE FABRICATION		8 hours
		f p-n junction, Bipolar junction transistor, JFET,	MOSFE	
		well, N-well & Twin top Process)		,
UNIT-IV		DESIGNING OF ANALOG AND DIGITAL CIRCUITS		8 hours
		for analog and digital ICs, functional elements available		
	-	Circuits-Inverter, Two Input NOR Gate, Two Input N	AND Gate	2.
Analog o	circuit	s– single stage CE Amplifier and Emitter Follower.		
UNIT-V		BICMOS ICs		8 hours
Design 1	rules	and Scaling, BICMOS ICs: Choice of transistor type	s, pnp tra	nsistors,
Resistor	s, cap	pacitors, Packaging: Chip characteristics, package fu	unctions,	package
operation	ns.			
Course O	utco	me: After successful completion of this course stud	ents will	be able to
CO 1		Identify different fabrication processes		
CO 2		Implement diffusion, ion implantation and different		

	types of lithography and etching.
CO 3	Explain Discrete devices and their fabrication.
CO 4	Design different digital logic circuits and analogcircuits
CO 5	Categorize BiCMOS ICs and their packaging.
Text books	
1. Peter Va	n Zant, Microchip fabrication, McGraw Hill, 1997.
2. S.M. Sze	e, VLSI technology, McGraw-Hill Book company, NY, 1988.
Reference Bo	oks
1. S.K. Gandh	i, 'VLSI Fabrication Principles'.
2. S.M. Sze, 'S	Semiconductor Devices Physics and Technology'.
3. Puckness D	ouglas A, Eshraghiaw Kamran "Basic VLSI Design" – Prentice Hall (India)
4. K.R. Botkar	, 'Integrated Circuits'

		M. TECH FIRST YEAR		
Course	Code	AMTVL0112	LTP	Credit
Course	Title	MOS Device Modeling	300	03
Course		tive:		
1	<u> </u>	dy and analysis of MOS structure, its operations a	and . MC	OS as a
_	capacit	• • •	,	
2	1	ly and analysis of MOSFET Device Characteristics.		
3		dy and analysis of Mobility models, MOS Performance	e parame	ters and
	its freq	uency limitations.	-	
4	To stuc	ly and analysis of SOI MOSFET.		
5	To stuc	ly and analysis of SPICE Models for Semiconductor De	evices.	
Pre-req	uisites	Basic Electronics Engineering		
-		Course Contents / Syllabus		
UNIT-I	.]	MOS PHYSICS		8 hours
		urfaces, Ideal MOS structure, MOS device in thermal ec	auilibrium	
		fferences, charges in oxide, interface states, band diagr	-	
		ctrostatics of a MOS (charge based calculations), calcul		
		hold voltage, MOS as a capacitor (2 terminal device),		
on thresh		•		lilliar woo, eneer
on un con	\mathbf{u}			
		<u> </u>		8 hours
UNIT-I	I]	MOSFET DEVICE CHARACTERISTICS	eshold va	
UNIT-I Field-Eff	I] ect Tran	MOSFET DEVICE CHARACTERISTICS		oltages; output and
UNIT-I Field-Effe transfer	I] ect Tran character	MOSFET DEVICE CHARACTERISTICS sistors: MOSFET- basic operation and fabrication; thr ristics of MOSFET, short channel and Narrow width	effects,	oltages; output and MOSFET scaling,
UNIT-I Field-Effe transfer c Small sig	I [] ect Tran character mal mod	MOSFET DEVICE CHARACTERISTICS sistors: MOSFET- basic operation and fabrication; thr ristics of MOSFET, short channel and Narrow width leling for low frequency and High frequency, high-k ga	effects,	oltages; output and MOSFET scaling,
UNIT-I Field-Effe transfer of Small sig junctions	I ect Tran character nal mod , source	MOSFET DEVICE CHARACTERISTICS isistors: MOSFET- basic operation and fabrication; thr ristics of MOSFET, short channel and Narrow width leling for low frequency and High frequency, high-k ga and drain resistance.	effects,	oltages; output and MOSFET scaling, trics, ultra-shallow
UNIT-I Field-Effe transfer c Small sig	I dect Tran character nal mod , source II d	MOSFET DEVICE CHARACTERISTICS isistors: MOSFET- basic operation and fabrication; thr ristics of MOSFET, short channel and Narrow width leling for low frequency and High frequency, high-k ga and drain resistance. MOBILITY MODELS AND MOS	effects,	oltages; output and MOSFET scaling, trics, ultra-shallow
UNIT-I Field-Effe transfer of Small sig junctions UNIT-I	I	MOSFET DEVICE CHARACTERISTICSasistors: MOSFET- basic operation and fabrication; thrristics of MOSFET, short channel and Narrow widthleling for low frequency and High frequency, high-k gaand drain resistance.MOBILITY MODELS AND MOSPERFORMANCE PARAMETERS	effects, ate dielec	oltages; output and MOSFET scaling, trics, ultra-shallow 10 hours
UNIT-I Field-Effe transfer of Small sig junctions UNIT-I Low field	I I ect Tran character gnal mod , source II I I	MOSFET DEVICE CHARACTERISTICS asistors: MOSFET- basic operation and fabrication; thr ristics of MOSFET, short channel and Narrow width leling for low frequency and High frequency, high-k ga and drain resistance. MOBILITY MODELS AND MOS PERFORMANCE PARAMETERS y, high field mobility, mobility various models, on curr	effects, ate dielec	oltages; output and MOSFET scaling, trics, ultra-shallow 10 hours cteristics, off current
UNIT-I Field-Effe transfer of Small sig junctions UNIT-I Low field characteris	I I ect Tran character gnal mod , source II I nobilit stics, sub	MOSFET DEVICE CHARACTERISTICS asistors: MOSFET- basic operation and fabrication; thr ristics of MOSFET, short channel and Narrow width leling for low frequency and High frequency, high-k ga and drain resistance. MOBILITY MODELS AND MOS PERFORMANCE PARAMETERS y, high field mobility, mobility various models, on curr threshold swing, effect of interface states on sub threshold	effects, ate dielec rent charac d swing, d	oltages; output and MOSFET scaling, trics, ultra-shallow 10 hours cteristics, off current rain conductance and
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UNIT-I Field-Effe transfer of Small sig junctions. UNIT-I Low field characteris transcondu Modeling, UNIT-I Multiple g	I I ect Tran character gnal mod , source II I I stics, sub uctance, o , small sig V gate SOI	MOSFET DEVICE CHARACTERISTICS Isistors: MOSFET- basic operation and fabrication; thr ristics of MOSFET, short channel and Narrow width leling for low frequency and High frequency, high-k ga and drain resistance. MOBILITY MODELS AND MOS PERFORMANCE PARAMETERS y, high field mobility, mobility various models, on curr o threshold swing, effect of interface states on sub threshold effect of source bias and body bias on threshold voltage and gnal model for low, medium and high frequencies. THE SOI MOSFET MOSFETs: double gate, FINFET, comparison of capacitance	a effects, ate dielec rent charac d swing, d d device op ces with bu	oltages; output and MOSFET scaling, trics, ultra-shallow 10 hours cteristics, off current rain conductance and peration, Large signal 6 hours ilk MOSFET, PD and
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UNIT-I Field-Effe transfer of Small sig junctions. UNIT-I Low field characteris transcondu Modeling, UNIT-I Multiple g FD SOI d impact ion BJT effect	I I ect Tran I character I gate SOI I evices, s I izate SOI I evices, s I izate SOI I evices, s I	MOSFET DEVICE CHARACTERISTICS Isistors: MOSFET- basic operation and fabrication; thr ristics of MOSFET, short channel and Narrow width leling for low frequency and High frequency, high-k ga and drain resistance. MOBILITY MODELS AND MOS PERFORMANCE PARAMETERS y, high field mobility, mobility various models, on curr o threshold swing, effect of interface states on sub threshold effect of source bias and body bias on threshold voltage and gnal model for low, medium and high frequencies. THE SOI MOSFET MOSFETs: double gate, FINFET, comparison of capacitance hort channel effects: Kink effect and Hot-carrier degradati eating.	a effects, ate dielec rent charac d swing, d d device op ces with bu	oltages; output and MOSFET scaling, trics, ultra-shallow 10 hours cteristics, off current rain conductance and peration, Large signal 6 hours ilk MOSFET, PD and odel and C-∞ model ng body and parasitic
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CO 3	Explain and analyse the Mobility models, MOS Performance parameters and its frequency limitations.
CO 4	Explain and analyse SOI MOSFET.
CO 5	Explain and analyse SPICE Models for Semiconductor Devices.
Fext Bo	oks
	H. Nicollian, J. R. Brews, Metal Oxide Semiconductor - Physics and Technology, John ley and Sons.
Te	ndita Das Guptha, Amitava Das Guptha, Semiconductor Devices Modeling and chnology, Prentice Hall India
	n- PierrieColinge, Silicon-on-insulator Technology: Materials to VLSI, Kluwer Academic blishers group.
Referen	ce Books
	Colinge, "FinFETs and Other Multi-Gate Transistors", Springer. 2009 nnis Tsividis, Operation and Modeling of the MOS transistor, Oxford University Press.
Video I	Lecture Links:
Unit I:	
https://y	vww.youtube.com/watch?v=KohWxkovp0k
	www.youtube.com/watch?v=CT6olzelSKQ
	ocw.tudelft.nl/course-lectures/semiconductor-junction/
Unit II	•
	www.youtube.com/watch?v=0C4uxtS-tlQ
-	www.youtube.com/watch?v=XcDeh98ppXk
-	www.youtube.com/watch?v=uHTyw4GGnRo
-	www.youtube.com/watch?v=xSh9PZZPpOc
Unit II	
	www.youtube.com/watch?v=4m49vM0Ryt8
-	vww.youtube.com/watch?v=xgYdLvWcvms
	www.youtube.com/watch?v=IrbGAgrcvic
Unit IV	
0	• vww.youtube.com/watch?v=WWjldCmRteg
	www.youtube.com/watch?v=syRQTHF88eQ
	nptel.ac.in/courses/113/104/113104012/
-	www.youtube.com/watch?v=vS3S1KfNLhE
Unit V	
	nptel.ac.in/courses/117/106/117106033/
	www.digimat.in/nptel/courses/video/108107129/L04.html
1	www.digimat.in/nptel/courses/video/10810/129/L04.html
-	• •
	www.coursera.org/lecture/averagedswitchmodelingandsimulation/spice-simulation- e-pJ99m
example	C-DJ77111

NPTEL course video link: https://nptel.ac.in/courses/117/106/117106033/

	M. TECH FIRST YEAR		
Course Code	AMTVL0113	LTP	Credit
Course Title	Analog IC Design	300	03
Course Object	tive:		
· · · · ·	To develop the ability to design and analyze MOS based		
	Analog VLSI circuits.		
2	To analyze the performance of single stage amplifier		
3	To develop the skills to design Differential Amplifier		
	circuits for a given specification.		
	Analyze the frequency response of the different		
	configurations of an amplifier		
	To provide the knowledge of operational amplifier & feedback topologies		
	feedback topologies.		
Pre-requisites	: Basic electronics devices, Semiconductor & Amplifiers		
	Course Contents / Syllabus		
UNIT-I	BASIC MOS DEVICE PHYSICS	8	hours
	tions, MOSFET as a Switch, MOS I/V Characteristics, Se		
	lels, MOS Device Capacitances, NMOS versus PMOS Dev	vices, Lor	ng-Channel
versus Short-Chan			
	SINGLE-STAGE AMPLIFIERS		8 hours
	ommon-Source Stage, Common-Source Stage with Resistive		÷
	Load, CS Stage with Current-Source Load, Source Follower, C	Common-(Gate Stage,
Cascode Stage, Fol			
	DIFFERENTIAL AMPLIFIERS		8 hours
	Differential Operation, Basic Differential Pair, Commo		
	ith MOS Loads, Gilbert Cell, Passive and Active Current Mi		sic Current
	Current Mirrors, Active Current Mirrors, Common-Mode Prop	erties	0.1
0111111	FREQUENCY RESPONSE OF AMPLIFIERS		8 hours
	tions, Miller Effect, Association of Poles with Nodes, Cor		
	Common-Gate Stage, Cascode Stage, Differential Pair, Noise	in Differ	ential Pairs
	ies, Effect of Loading, Effect of Feedback on Noise OPERATIONAL AMPLIFIERS		0 1
			8 hours
	tions, Performance Parameters, One-Stage Op Amps, Two-Sta		
Supply Rejection.	rison, Common-Mode Feedback. Input Range Limitations	s, slew K	ale, Power
	more After an energy learning of this course study	.4.a:11 h	a ablata
Course Oulco	me: After successful completion of this course studer	its will d	e able to
CO 1	Draw the equivalent circuits of MOS based Analog VLSI and	nd	
	analyse their performance.		
CO 2	Design analog VLSI circuits for a given specification.		
CO 3	Analyse the frequency response of the different configuration	ns	
	of an amplifier.		
	Analyse the feedback topologies involved in the amplifier		
	design.		
	Appreciate the design features of the differential amplifiers.		
	-		

Text books
1. Razavi, "Design of Analog CMOS Integrated Circuits", 2nd Edition, McGraw Hill Edition
2016.
2. Paul. R.Gray&Robert G. Meyer, "Analysis and Design of Analog Integrated Circuits",
Wiley, 5th Edition, 2009.
3. R. Gregorian and Temes, "Analog MOS Intgrated Circuits for Signal Processing", Wiley
Publications
Reference Books
1. Ken Martin, "Analog Integrated Circuit Design", Wiley Publications.
2. Sedra and Smith, "Microelectronic Circuits", Oxford Publications.
3. B.Razavi, "Fundamentals of Microelectronics", Wiley Publications

	M. TECH FIRST YEAR			
Course Code	AMTVL0114 L	T	Р	Credit
Course Title		0		03
Course Object	ive:			
1	To analyze the basic stages of manufacturing and cryst	al g	rowt	h.
2	To evaluate the process of wafer preparation and oxida			
3	To analyze the lithography and etching process			
4	To explain process of diffusion and ion implantation.			
5	To learn the basic process involved in metallization and	d pa	ickag	ging
Pre-requisites:	Basics of semiconductors and their properties.			
	Course Contents / Syllabus			
UNIT-I	OVERVIEW OF SEMICONDUCTOR INDUSTRY	r	8	hours
Semiconductor Si Quality.	aterial properties, Crystal growth, Basic wafer fabri licon Preparation, Czochralski (CZ) method, Float zone,			and Wafer
UNIT-II	WAFER FABRICATION			8 hours
Layering , Patter	reparation, Wafer Terminology, Basic Wafer-Fabric rning, Doping, Heat treatments, Circuit design, mass, Oxidation: Dry and wet oxidation, Clean room Constr	ask	s, E	
UNIT-III	LITHOGRAPHY AND ETCHING			8 hours
	g process, Lithography: Optical Lithography, Electron	bea	m li	thography,
	Chemical Etching, Dry etching Wet etching.			
UNIT-IV	DOPING AND DEPOSITION			8 hours
Implantation: Ion	ositions: Diffusion process steps, deposition, Drive-i- -Implantation Technique, Implantation Equipment, C w pressure CVD systems, Plasma enhanced CVD syste	VD	bas	sics, CVD
UNIT-V	METALLIZATION AND PACAKAGING			e hours
	Internation Application, Metallization Choices,	Dhr		8 hours
Deposition, Vacua Types, Packaging	Im Deposition, Sputtering Apparatus. Packaging of VLS Design Consideration, Package Fabrication Technologie ne: After successful completion of this course studer	I de s.	evice	s: Package
CO 1	Analyze the basic stages of manufacturing and crystal			
CO 2	Evaluate the process of wafer preparation and oxidation		, .11.	
		1.		
CO 3	Analyze the lithography and etching process.			
CO 4	Explain the process of diffusion and ion implantation.			
CO 5	Learn the basic process involved in metallization and p	ack	agin	g
Text books				
1. Peter Van Zant	, Microchip fabrication, McGraw Hill, 1997.			

2. S.M. Sze, VLSI technology, McGraw-Hill Book company, NY, 1988
Reference Books
1. Wani-Kai Chen (editor), The VLSI Hand book, CRI/IEEE press, 2000
2. C.Y. Chang and S.M. Sze, ULSI technology, McGraw Hill, 2000
3. S.K. Ghandhi, "VLSI Fabrication Principles", Willy-India Pvt. Ltd, 2008.
4. J. D. Plummer, M. D. Deal and Peter B. Griffin, "Silicon VLSI Technology:
Fundamentals, Practice and Modeling", Pearson Education Publication, 2009

	M. TECH FIRST YEAR		
Course Code	AMTVL0115	LT P	Credit
Course Title	Clean Room Technology And Maintenance	300	03
Course Objecti	ve:		
1	Study and explain cleanroom standards and	ancillary	
	cleanrooms.		
2	Knowledge about clean room fabrication environment.		
3	Identify the various filtration mechanisms.		
4	Categorize cleanroom testing and monitoring system.		
5	Analyze air quantities, pressure differences and clean r disciplines.	room	
Pre-requisites:	Basics of IC Technology		
•	Course Contents / Syllabus		
UNIT-I	INTRODUCTION TO CLEAN ROOM TECHNOI	LOGY	8 hours
Clean room star	room Classification Standards, Unidirectional air flow dards, Federal Standards 209, ISO standard 146 naceutical, cleanrooms)		
UNIT-II	CLEAN ROOM ENVIRONMENT		8 hours
	ntly Ventilated and Ancillary Cleanrooms, Mini enviro	onments, is	
RABS, Containme	nt zone, Construction and clean build, Design of Unidire	ctional Cle	eanrooms.
UNIT-III	FILTRATION MECHANISM		8 hours
High Efficiency A	r filtration, Particle removal mechanisms, testing of high	efficiency	filters.
UNIT-IV	TESTING & MONITORING SYSTEM		8 hours
	and Monitoring, Principles of cleanroom testing, Testinn state, Monitoring of cleanroom.	ng in relat	ion to room
UNIT-V	CLEAN ROOM STANDARD PARAMETERS		8 hours
	ir Quantities and Pressure Differences, Air movement	control. Re	
	m containment leak testing.	•••••••••	
Course Outcon	ne: After successful completion of this course studen	ts will be a	ble to
	L L		
CO 1	Specify cleanroom standards and ancillary cleanrooms		
	•		
CO 1	Specify cleanroom standards and ancillary cleanrooms		
CO 1 CO 2	Specify cleanroom standards and ancillary cleanrooms Explain about clean room fabrication environment.		
CO 1 CO 2 CO 3	Specify cleanroom standards and ancillary cleanrooms Explain about clean room fabrication environment. Identify the surface finishes and filtration mechanisms.		
CO 1 CO 2 CO 3 CO 4	Specify cleanroom standards and ancillary cleanrooms Explain about clean room fabrication environment. Identify the surface finishes and filtration mechanisms. Categorize cleanroom testing and monitoring system. Analyze air quantities, pressure differences and clean r		

2. Matts Ramstorp, Introduction to Contamination Control and Cleanroom Technology, Wiley, 2008.

Reference Books

1. Wani-Kai Chen (editor), The VLSI Hand book, CRI/IEEE press, 2000

Link:	
Unit 1	https://www.youtube.com/watch?v=8uGZMyjFugg
Unit 2	https://www.youtube.com/watch?v=YAouXIS_FSU
Unit 3	https://www.youtube.com/watch?v=wSSfOqEQClc
Unit 4	https://www.youtube.com/watch?v=aBIxPo0p7dc
Unit 5	https://www.youtube.com/watch?v=lHmHYWdH8Ug

	M. TECH FIRST YEAR		
Course Code	AMTVL0116 L	ТР	Credit
Course Title	ULSI Technology 3	00	03
Course Objecti	ve:		
1	To study the basics of chip fabrication and clean room.		
2	To learn the ion implantation and variousOxidation technolo	ogies.	
3	To study the classification of lithographic techniques.		
4	To identify various metallization schemes.		
5	To explain the concept of Memories.		
Pre-requisites:	Microelectronics		
	Course Contents / Syllabus		
UNIT-I	CLEAN ROOM AND WAFER PREPARATION		8 hours
Environment for U	JLSI technology: clean room and safety requirements, Wafer	cleanin	g process and
wet chemical etc	hing techniques ,Microelectronics and microscopy, ULSI	proces	s technology,
Application of TEN	M for construction analysis, TEM sample preparation technique	es.	
UNIT-II	IMPURITY INCORPORATION		9 hours
	on modelling and technology, Ion implantation: modelling, tec erization of impurity profiles.	nnolog	y and damage
annealing; Charact Oxidation: kinetic		nin filr	ns. Oxidation
annealing; Charact Oxidation: kinetic	erization of impurity profiles. es of silicon dioxide growth for thick, thin and ultra-th	nin filr	ns. Oxidation JLSI.
annealing; Charact Oxidation: kinetic technologies in UL UNIT-III	erization of impurity profiles. es of silicon dioxide growth for thick, thin and ultra-th SI; Characterization of oxide films; high K and low K dielectric	nin filr	ns. Oxidation JLSI.
annealing; Charact Oxidation: kinetic technologies in UL UNIT-III Photolithography t Chemical Vapour	erization of impurity profiles. es of silicon dioxide growth for thick, thin and ultra-th SI; Characterization of oxide films; high K and low K dielectric LITHOGRAPHIC TECHNIQUES echniques for VLSI/ULSI; Mask generation. deposition techniques: CVD techniques for deposition of	nin filr ics for U	ns. Oxidation JLSI. 9 hours ilicon, silicon
annealing; Charact Oxidation: kinetic technologies in UL UNIT-III Photolithography t Chemical Vapour dioxide, silicon ni	erization of impurity profiles. es of silicon dioxide growth for thick, thin and ultra-th SI; Characterization of oxide films; high K and low K dielectric LITHOGRAPHIC TECHNIQUES echniques for VLSI/ULSI; Mask generation. deposition techniques: CVD techniques for deposition of tride and metal films; epitaxial growth of silicon; modelling	hin film cs for U f polys and te	ns. Oxidation JLSI. 9 hours ilicon, silicon chnology. Ion
annealing; Charact Oxidation: kinetic technologies in UL UNIT-III Photolithography t Chemical Vapour dioxide, silicon ni implantation and	erization of impurity profiles. es of silicon dioxide growth for thick, thin and ultra-th SI; Characterization of oxide films; high K and low K dielectric LITHOGRAPHIC TECHNIQUES echniques for VLSI/ULSI; Mask generation. deposition techniques: CVD techniques for deposition of tride and metal films; epitaxial growth of silicon; modelling substrate defects, Dielectrics and isolation, Silicides, po	hin film cs for U f polys and te	ns. Oxidation JLSI. 9 hours ilicon, silicon chnology. Ion
annealing; Charact Oxidation: kinetic technologies in UL UNIT-III Photolithography t Chemical Vapour dioxide, silicon ni implantation and Metallization and i	erization of impurity profiles. es of silicon dioxide growth for thick, thin and ultra-th SI; Characterization of oxide films; high K and low K dielectric LITHOGRAPHIC TECHNIQUES echniques for VLSI/ULSI; Mask generation. deposition techniques: CVD techniques for deposition of tride and metal films; epitaxial growth of silicon; modelling substrate defects, Dielectrics and isolation, Silicides, po nterconnects.	hin film cs for U f polys and te	ns. Oxidation JLSI. 9 hours ilicon, silicon chnology. Ion and salicide,
annealing; Charact Oxidation: kinetic technologies in UL UNIT-III Photolithography t Chemical Vapour dioxide, silicon ni implantation and Metallization and i UNIT-IV	erization of impurity profiles. es of silicon dioxide growth for thick, thin and ultra-th SI; Characterization of oxide films; high K and low K dielectric LITHOGRAPHIC TECHNIQUES echniques for VLSI/ULSI; Mask generation. deposition techniques: CVD techniques for deposition of tride and metal films; epitaxial growth of silicon; modelling substrate defects, Dielectrics and isolation, Silicides, pointerconnects. METALLIZATION TECHNIQUES	f polys and te	ns. Oxidation JLSI. 9 hours ilicon, silicon chnology. Ion and salicide, 8 hours
annealing; Charact Oxidation: kinetic technologies in UL UNIT-III Photolithography t Chemical Vapour dioxide, silicon ni implantation and Metallization and i UNIT-IV Evaporation and	erization of impurity profiles. es of silicon dioxide growth for thick, thin and ultra-th SI; Characterization of oxide films; high K and low K dielectric LITHOGRAPHIC TECHNIQUES echniques for VLSI/ULSI; Mask generation. deposition techniques: CVD techniques for deposition of tride and metal films; epitaxial growth of silicon; modelling substrate defects, Dielectrics and isolation, Silicides, po nterconnects. METALLIZATION TECHNIQUES sputtering techniques. Failure mechanisms in metal inter	f polys and te lycide	ns. Oxidation JLSI. 9 hours ilicon, silicon chnology. Ion and salicide. 8 hours ts; multilevel
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CO 4	Explain and analyze metallization schemes.	
CO 5	Design semiconductor memories.	

Text books

1. S.M. Sze(2nd Edition)"VLSI Technology", McGraw Hill Companies Inc.

2. Chih-Hang Tung, George T.T. Sheng, Chih-Yuan Lu, ULSI Semiconductor Process Technology Atlas, John Wiley & Sons, 2003.

3. C.Y. Chang and S.M. Sze (Ed), "ULSI Technology", 2000, McGraw Hill Companies Inc.

Reference Books

1. Stephena, Campbell, "The Science and Engineering of Microelectronic Fabrication", Second Edition, Oxford University Press.

2. James D. Plummer, Michael D. Deal, "Silicon VLSI Technology" Pearson Education Reading.

	M. TECH FIRST YEAR		
Course Code	AMTVL0201	LT P	Credit
Course Title	Digital Design using FPGA and CPLD	300	03
Course Objecti	ve:		
1	To study finite state machines and its realization.		
2	To study asynchronous Sequentialmachine.		
3	To learn Designing of Digital logic using PLD.		
4	To get knowledge of different FPGA series.		
5	To study different CPLD series.		
Pre-requisites:	Basics of CMOS and Fabrication.		
	Course Contents / Syllabus		
UNIT-I	FINITE STATE MACHINE (FSM)	81	iours
from verbal descri State Machine, Intr	gn Strategies, Mealy & Moore model, Realization of State Diption, Minimization of State Table from completely & Incroduction to Algorithmic State Machine.	0	y specified
UNIT-II	ASYNCHRONOUS SEQUENTIAL CIRCUIT		8 hours
		-	
UNIT-III	PROGRAMMABLE LOGIC DEVICES (PLD)		8 hours
	ecture, Features & Digital Design of ROM, EPROM, EEPROM Design of a keypad scanner using PLD.	, Flash M	emory,
UNIT-IV	FIELD PROGRAMMABLE GATE ARRAY (FPGA)		8 hours
Xilinx FPGA XC4	ing architecture, Design flow, Technology Mapping for FPGA 000, Comparative Study of Xilinx (ZU11EG) & Intel (Stra reference to cortex A53.		(650 series
UNIT-V	COMPLEX PROGRAMMABLE LOGIC DEVICES (CPLD)		8 hours
(Mach 1 to 5), Cy Speed performance	 x 5000/7000 series and Altera FLEX logic- 10000 series CP press FLASH 370 Device technology, Lattice plsi architecta and system programmability. After completion of this course students will be able to a student of the s	ures – 30	
CO 1	Realize finite state machines.		
CO 2	Formulate asynchronous Sequentialmachine.		
CO 3	Design Digital logic using PLD.		
CO 4	Explain different FPGA series.		
CO 5	Explain different CPLD series.		

- 1. P. K. Chan& S. Mourad, Digital Design using Field Programmable Gate Array, Prentice Hall.
- 2. Charles H Roth, Jr., "Digital Systems Design Using VHDL", PWS, 1998.
- 3. S. Trimberger, Edr., Field Programmable Gate Array Technology, Kluwer Academic Pub.

Reference Books

- 1. J. Old Field, R. Dorf, Field Programmable Gate Arrays, John Wiley& Sons, Newyork.
- 2. S.Brown, R.Francis, J.Rose, Z.Vransic, Field Programmable GateArray, Kluwer Pub.
- 3. Richard FJinder, "Engineering Digital Design," Academic press

M. TECH FIRST YEAR					
Course Code	AMTVL0202 LT P				
Course Title	Low Power VLSI Design300	03			
Course Objectiv	ve:				
1	To provide the knowledge of Low Power VLSI Chips a	nd			
	different losses associated with the CMOS Devices				
2	To provide the knowledge of Power estimation Simulation Power	r			
	analysis and Probabilistic power analysis of Design				
3	To provide the knowledge of circuit level and Logic level design				
4	To provide the knowledge of Low Power Architecture and system	n.			
5	To provide the basic knowledge of Low Power Clock Distribution	on			
	Algorithm & Architectural Level Methodologies				
Pre-requisites:	CMOS VLSI Design, Digital logic Design.				
	Course Contents / Syllabus				
UNIT-I	INTRODUCTION & DEVICE AND TECHNOLOGY	8 hours			
	IMPACT ON LOW POWER	0 110 11 1			
Introduction: Nee	ds for Low Power VLSI Chips, Sources of power dissipation on d	gital integrated			
circuit, Emerging lo	ow power approaches, Physics of power dissipation in CMOS Devi	ces,			
Device and techno	logy impact on low power: Dynamic dissipation on low power, T	ransistor sizing			
& gate oxide thick	ness, Impact of technology Scaling, Technology & Device innovat	ion			
UNIT-II	POWER ESTIMATION SIMULATION POWER ANALYS	IS 8 hours			
-	& PROBABILISTIC POWER ANALYSIS				
	Simulation Power analysis: - SPICE circuit simulators, Gate leve				
· 1	ive Power Estimation, Static State Power, Gate level Capacitance				
	analysis, Data Correlation Analysis in DSP systems. Monte Carlo				
-	er analysis:- Random Logic Signals. Probability & frequency, Prob	babilistic			
-	chniques, Signal Entropy.				
UNIT-III	LOW POWER DESIGN	8 hours			
	er Consumption in circuit level, Flip Flop & Latches design, Hi	gh Capacitance			
node, Low power d					
0	e Reorganisation, Signal gating, Logic encoding, state machine	encoding, Pre			
computation logic					
UNIT-IV	LOW POWER ARCHITECTURE AND SYSTEM	8 hours			
	ance Management, Switching Activity Reduction, Parallel Ar				
U	, Flow graph Transformation, Low Power Arithmetic Compone	nt, Low Power			
Memory Design					
UNIT-V	LOW POWER CLOCK DISTRIBUTION & ALGORITHM	8 hours			
	& ARCHITECTURAL LEVEL METHODOLOGIES	1 1			
	Example : Power dissipation in clock distribution, sin				
	zero skew Vs tolerable skew chip and package co-design of clock				
0	hitectural Level Methodologies:-Introduction, Design flow, Alg	jorithmic Level			
analysis and optimi	zation, Architectural level estimation and synthesis				

Course Outco	ome: After successful completion of this course students will be able to
CO 1	Identify different losses associated with the CMOS Devices.
CO 2	Explain the concept of Power estimation Simulation Power analysis and Probabilistic Power analysis of Design.
CO 3	Identify circuit and logic level low power design.
CO 4	Analyze the Low Power Architecture and system.
CO 5	Explain Low Power Clock Distribution Algorithm.
Text books	
1. Gary K. Y	Yeap, Practical Low Power Digital VLSI Design, KAP 2007
2. Rabaey, I	Pedram, "Low power design methodologies" Kluwer Academic, 1997
Reference Bo	oks
1. Kaushik l	Roy, Sharat Prasad, "Low-Power CMOS VLSI Circuit" Wiley 2000

M. TECH FIRST YEAR					
Course Co	ode	AMTVL0251	LTP	Credit	
Course Ti	tle	Digital Design using FPGA and CPLD Lab	0 0 4	02	
Pre-requi	Pre-requisites: Basics Knowledge of Digital Electronics & Digital System Design				
Sr. No.	List of	Experiment			
1	Demon	stration of FPGA and CPLD Boards.			
2	Design	& Implement the Boolean Expression Y=AB+BC+CA on CPLD.			
3	Design	& Implement Full adder and Full Subtractor on CPLD.			
4.	Design	& Implement (i) 2-bit comparator and (ii) 2-bit multiplier (iii) 8x1 M	/lultiplexer	on CPLD.	
5	Design	& Implement S-R, J-K, D and T Flip Flops on FPGA.			
6	Design & Implement (i) Universal shift register (ii) 4- bit UP-DOWN Synchronous Counter on FPGA.				
7	Design	& Implement the (i) 4-bit ALU (ii) 8- bit SRAM on FPGA.			
8	Design	& Implement 7- Segment Display Driver circuit using CPLD.			
9	Design	& Implement Sequence Detector Circuit to detect given sequence 10	0101010 on	FPGA.	
10	Modelling and Implementation of UART on FPGA.				
Lab Cou	rse Outc	come: After completion of this course students will be able to			
CO 1	Design	& Implement the Combinational Logic Circuits on CPLD.			
CO 2	Design	Design & Implement the Sequential Logic Circuits on CPLD.			
CO 3	Design & Implement the Memories on FPGA.				
CO 4	Design	& Implement UART on FPGA.			
Link:					
1	https://v	www.youtube.com/watch?v=9mpRF6bAY1g			
2	https://v	www.youtube.com/watch?v=EGDHXynlXMk			
3	https://v	www.youtube.com/watch?v=H2GyAIYwZbw			
4	https://v	www.youtube.com/watch?v=WKZgK3BKDIo			
5		www.youtube.com/watch?v=s3Dk4CEfNg4&list=PLJ5C_6qdAvBE index=6	LELTSPgz	YkQg3Hgcl	

M. TECH FIRST YEAR								
Course Code	AMTVL0252	LT P	Credit					
Course Title								
	DFTWARE TOOL: CADENCE – Tool Bundle Cons							
	ALOG & MIXED SIGNAL DESIGN FRONT END							
• Virtuoso(R) Spectre(R) Simulator REL MMSIM 7.1								
	• Virtuoso(R) Schematic Editor XL REL IC 6.1.0							
2. ANALOG BACK END TOOL								
2 DU	 Virtuoso(R) Layout Suite XL REL IC 6.1.0 3. PHYSICAL DOMAIN 							
3. F 11	 SOC Encounter - XL (aka Cadence (R) SOC Encou 	nter - GPS)						
Sr. No.	Name of Experiment							
1	I-V characteristics of long and short-channel MOS	SFET transisto	ors in CMOS					
	technology.							
2	The gate capacitance of an MOS transistor. (Gate Ca	pacitance v/s V	/GS).					
3	The impact of device variations on static CMOS inve		,					
4	The VTC of CMOS inverter as a function of supply	voltage and sub	ostrate bias.					
5	Dynamic power dissingtion due to charging and disa	harging consci	tancas					
5Dynamic power dissipation due to charging and discharging capacitances.6Short-circuit currents during transients and impact of load capacitance on short								
0	circuit current in a CMOS inverter.	ioau capacitai	ice on short-					
7	7 The VTC of a two-input NAND & NOR data dependency.							
8	The variable-threshold CMOS inverter and Combina							
9	The low-power / low voltage D-Latch circuit.							
10								
10	a. The Full Adder							
	b. The Binary Adder							
	c. The Multiplier							
	d. The Shifter.							
	e. The SRAM Cell							
	f. The DRAM Cell							
Lab Course O	utcome: After completion of this course students ar	e able to						
CO 1	Study and analyze the various parameters of MOS Tr	ransistor.						
CO 2	Study and analyze the different parameters of CM design.	OS inverter fo	or low power					
CO 3	Design and implement the combinational digital circuits for low power circuits.							
CO 4	Design and implement the sequential digital circuits	for low power	circuits.					
Link:								
Unit 1	https://www.youtube.com/watch?v=TFOO1JAll2Y							
	https://youtu.be/ruClwamT-R0							
Unit 2	https://www.analog.com/en/design-center/design-too	ols-and-calcula	tors/ltspice-					
	simulator.html		1					
	https://www.youtube.com/watch?v=OgO1gpXSUzU	J						

	https://nptel.ac.in/courses/111/106/111106134/
Unit 3	https://nptel.ac.in/courses/106/105/106105034/ https://www.youtube.com/watch?v=dqcfYTePRxQ https://www.youtube.com/watch?v=rEeqxozkdZ0
Unit 4	https://www.digimat.in/nptel/courses/video/106105034/L37.html
Unit 5	https://nptel.ac.in/courses/106/105/106105161/

		Credit 03	
Course Objective: 1 To provide an in-depth understanding of the importance ar principle of testing and verification of faults affecting VLS circuits. 2 To provide the knowledge of the testing and testability of combinational circuits. 3 To provide the knowledge of the testing and testability of sequential circuits. 4 To provide the knowledge of the testing and testability of sequential circuits. 5 To provide an in-depth understanding of the memory designering methods. 5 To provide the basic knowledge of Built in self-test (BIST Techniques.) Pre-requisites:Digital and analog IC fabrication. Course Contents / Syllabus UNIT-I INTRODUCTION TO VLSI TESTING AND FAULT MODELING Importance and Principle of testing, Challenges in VLSI testing, Levels of abstra	nd	03	
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Course Contents / Syllabus UNIT-I INTRODUCTION TO VLSI TESTING AND FAULT MODELING Importance and Principle of testing, Challenges in VLSI testing, Levels of abstra)		
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UNIT-I INTRODUCTION TO VLSI TESTING AND FAULT MODELING Importance and Principle of testing, Challenges in VLSI testing, Levels of abstra			
	IT-I INTRODUCTION TO VLSI TESTING AND FAULT		
	actions	in VLSI	
	problem	i, Types of	
Testing, DC and AC parametric tests			
Fault Modeling: Stuck at fault, fault equivalence, fault collapsing, fault dominar		t simulation	
UNIT-II TESTING AND TESTABILITY OF COMBINATION. CIRCUITS	AL	8 hours	
Test Generation Basics: Test generation algorithms, Random test generation, AT			
$combinational\ circuits,\ Boolean\ difference,\ Path\ sensitization,\ D-algorithm,\ Sensitization,\ Sensitization,\ D-algorithm,\ Sensitization,\ Se$	ODEM,	Testable	
combinational logic circuit design			
UNIT-III TESTING AND TESTABILITY OF SEQUENTIAL CIRCUITS		8 hours	
Testing of sequential circuits as iterative combinational circuits, state table verif	ication,	test	
generation based on circuit structure, Sequential ATPG,			
Ad Hoc design rules, scan path technique (scan design), partial scan, Boundary s	scan		
UNIT-IV MEMORY, DELAY, FAULT AND IDDQ TESTING	14 D	6 hours	
Testable memory design, RAM fault models, Test algorithms for RAM, Delay f IDDQ testing, Testing methods, Limitations of IDDQ testing	aults, D	elay tests,	
UNIT-V BUILT IN SELF-TEST (BIST) TECHNIQUES		8 hours	
Built-in self-test (BIST): Design rules, Exhaustive testing, Pseudo-random testi	ng, Pse		
testing, Output response analysis, Logic BIST architectures, Introduction to Test	t compr	ession	
Course Outcome: After successful completion of this course students wi	ll be ab	le to	
CO 1 Apply the concepts in testing which can help them de better yield in IC design	acian o		

CO 2	Analyse the various test generation methods for combinational circuits.	
CO 3	Analyse the various test generation methods for sequential circuits.	
CO 4	Identify the design for testability methods for different memory circuits.	
CO 5	Recognize the BIST techniques for improving testability.	
Text books		
	ction to Logic Circuit Testing - Parag K. Lala, (Morgan & Claypool)	
	l and Vishwani D. Agrawal, (Kluwar Academic Publishers 2000)	unts - Milender
	tem Testing and Testable Design - M. Abramovici, M.Breuer, and A. lishing House)	Friedman
Reference Boo	ks	
1. Introduction to	o Formal Hardware Verification - Thomas Kropf (Springer)	
2. VLSI Test Pri Publishers. 20	inciples and Architectures Design for Testability – W.W. Wen (Morg 06)	gan Kaufmann
3. Digital System Publishing Ho	ns and Testable Design - M.Abramovici, M.A. Breuer and A.D. Frouse)	iedman (Jaico
4. Design Test International)	for Digital IC's and Embedded Core Systems - A.L. Crouch (Prentice Hall

Link:	
Unit 1	https://youtu.be/u_XLaTTzXaE
Unit 2	https://nptel.ac.in/courses/106/103/106103116/
Unit 3	https://nptel.ac.in/courses/106/103/106103116/
Unit 4	https://nptel.ac.in/courses/106/103/106103116/
Unit 5	https://nptel.ac.in/courses/106/103/106103116/

	M. TECH FIRST YEAR			
Course Code	AMTVL0212	LTP	Cr	edit
Course Title	VLSI DSP Architectures	300	()3
Course Object	tive:			
1	To explain basics of DSP processors and micro	program	nming	
	approaches.			
2	To learn building a data path and control path.			
3	To outline pipelining and pipe lined data path.			
4	To analyzeA/D and D /A converters and DSP computa			
5	To identify thearchitectures for programmable processing devices.	digital s	signal	
Pre-requisites	: VLSI DSP Architecture			
-	Course Contents / Syllabus			
UNIT-I	BASICS OF DSP PROCESSORS		8 h	ours
	s of Instruction set architectures of DSP processo	rs Micro		
	plementation of control part of the processor, CPU per		1 0	
evaluating perform		10111141100	und no	140001
UNIT-II	DATA PATH		Q) hour
	gic design conventions, building a data path, a simple in	mplement		
	mentation, simplifying control design.	mpiement	ution se	menne,
UNIT-III	PIPELINING		C) hour
<u></u>	ipelining, a pipe lined data path, pipe lined control, data	hazards a	-	
1	ich hazards, advanced pipelining: extracting more perfor			urung,
UNIT-IV	CONVERSIONS		8	8 hour
	for signals and coefficients in DSP systems, dynan	nic range		
	in DSP implementations, A/D conversion errors, and D			
D /A conversion	-	I I I		
UNIT-V	PROGRAMMABLE PROCESSORS		8	3 hour
architectural feat	architectures for programmable digital signal pro- ures, DSP computational building blocks, bus archi ess generation unit, speed issues, features for external int	tecture, d		
Course Outco	me: After successful completion of this course stude	nts will b	e able t	to
CO 1	Identify basics of DSP processors and micro approaches.	program	nming	
CO 2	Learn building a data path and control path.			
CO 3	Analyze pipelining and pipe lined data path.			
CO 4	CalculateA/D and D /A converters and DSP computation	onal error	·s.	
CO 5	Implement architectures for programmable digital sig devices.	nal proce	essing	_
Text books				
1. D. A, Patterson	and J.L Hennessy, "Computer Organization and Design	: Hardwa	re/ Soft	ware
	l., Elsevier, 2011.			

2. A. S Tannenbaum, "Structural Computer organization", 4th Ed., Prentice-Hall, 1999. **Reference Books**

 W. Wolf, "Modern VLSI Design: System on Silicon", 2nd Ed., Person Education,1998.
 Keshab Parhi, "VLSI Digital Signal Processing system design and implementations", Wiley1999.

		M. TECH FIRST YE	CAR		
Course	e Code	AMTVL0213	LT P	Credit	t
Course	e Title	Full Custom Design	300	03	
Course	e Objectiv	2.			
		be familiar with the schematic fundamental	s and layout designs	flow.	
		come to know about standard library cells a			
	basic cells.	5	51		
3 5	Students will	be able to design interconnect layout and ki	now special electrical	1	
	requirements				
		be able to incorporate special design rules a		es.	
5 5	Students will	be able to learn various kind of CAD tools.			
Pre-re	quisites: Ba	sics of VLSI			
		Course Contents / Syll	labus		
UNIT-	Ι	INTRODUCTION		8 k	ours
Introduc	tion: Schen	atic fundamentals, Layout design, Intro	duction to CMOS	VLSI ma	nufacturing
processe	es, Layers a	nd connectivity, Process design rules Sign	ificance of full cust	om IC des	ign, layout
design f	lows.				
UNIT-	II	SPECIALIZED BUILDING BLOCKS			8 hours
Advance	ed technique	s for specialized building blocks Standard c	ell libraries, Pad cell	s and Laser	fuse cells,
Power g	rid Clock sig	nals and Interconnect routing.			
UNIT-		LAYOUT DESIGNS			8 hours
Intercon	nect layout o	lesign, Special electrical requirements, Lay	out design technique	es to addres	s electrical
characte	ristics.				
UNIT-	IV	LAYOUT CONSIDERATIONS			8 hours
•		ns due to process constraints Large metal	1	1	•
Special	design rules,	Latch-up and Guard rings, Constructing the	e pad ring, Minimizin	ng Stress ef	fects.
UNIT-	V	LAYOUT CAD TOOLS			8 hours
Proper la	ayout CAD t	ools for layout, Planning tools, Layout gene	eration tools, Support	tools.	
Course	e Outcome	: After successful completion of this cou	rse students will be	able to	
CO	1 Desig	n layout with schematic.			
CO	2 Differ	entiate standard cells and other types of cell	ls.		
CO	3 Do th	e electrical connections and interconnect lay	yout designs.		
CO	4 Tackl	e with the minimization of stress effects.			
CO	5 Demo	nstrate the layout tools, generation tools, et	с.		
Text b	ooks			•	
1.Dan C	lein, CMOS	IC Layout Concepts Methodologies and To	ols, Newnes, 2000.		
2.Ray A	lan Hastings	, The Art of Analog Layout, 2nd Edition, Pr	rentice Hall, 2006		
Refere	nce Books				
1. CMO	S: Circuit De	esign, Layout, and Simulation by R. Jacob E	Baker. 3rd Edition.		

M. TECH FIRST YEAR			
Course Code	AMTVL0214	LT P	Credit
Course Title	MEMS Sensor Design	300	03
Course Object			
1		brication	
2	To provide the knowledge about Mechanics of Bean Diaphragm Structures.	n and	
3	To provide the knowledge about drag effect of a fluid damping and its models.	d, Air	
4	To provide the knowledge of Electrostatic Actuation	1.	
5	To provide the basic knowledge of MEMS Structure Systems in RF applications.	es and	
Pre-requisites:	Basics of sensors.		
	Course Contents / Syllabus		
UNIT-I	INTRODUCTION TO MEMS		8 hours
	on Technologies, Materials and Substrates for M	EMS. Pro	
	Sensors/Transducers, Piezoresistive Effect, Piezoelec		
Sensor.		•	
UNIT-II	MECHANICS OF BEAM AND DIAPI STRUCTURES	HRAGM	8 hours
Stress and Strain,	Hooke's Law. Stress and Strain of Beam Structure	s: Stress,	Strain in a
Bent Beam, Bendi	ng Moment and the Moment of Inertia, Displacemen	nt of Beam	Structures
Under Weight, Ber	nding of Cantilever Beam Under Weight.		
UNIT-III	AIR DAMPING		8 hours
Drag Effect of a Fluid: Viscosity of a Fluid, Viscous Flow of a Fluid, Drag Force Damping, The Effects of Air Damping on Micro-Dynamics. Squeeze-film Air Damping: Reynolds' Equations for Squeeze-film Air Damping, Damping of Perforated Thick Plates. Slide-film Air Damping: Basic Equations for Slide-film Air Damping, Couette-flow Model, Stokes- flow Model.			
UNIT-IV	ELECTROSTATIC ACTUATION		8 hours
Electrostatic Force of Mechanical Ac	Electrostatic Forces, Normal Force, Tangential Force, Fringe Effects, Electrostatic Driving of Mechanical Actuators: Parallel-plate Actuator, Capacitive sensors. Step and Alternative Voltage Driving: Step Voltage Driving, Negative Spring Effect and Vibration Frequency.		
UNIT-V	MEMS STRUCTURES AND SYSTEMS APPLICATIONS	IN RF	8 hours
	Resonators, Beam Resonators, Coupled-Resonator Bandpass Filters, Film Bulk Acoustic Resonators, Microelectromechanical Switches: Membrane Shunt Switch, Cantilever Series		
Course Outcon	Course Outcome: After successful completion of this course students will be able to		be able to
CO 1	Identify MEMs fabrication Technologies.		

CO 2	Analyse Mechanics of Beam and Diaphragm Structures.		
CO 3	Explain drag effect of a fluid, Air damping and its models.		
CO 4	Design different Electrostatic Actuators.		
CO 5	Explain MEMS Structures and Systems in RF applications.		
Text books			
1. Minhang H	1. Minhang Bao, 'Analysis and Design Principles of MEMS Devices', First edition		
2005, Elsevier.			
2. Nadim Ma	2. Nadim Maluf, KirtWilliums, 'An Introduction to Microelectromechanical Systems		
Engineering',2nd ed., Artech House microelectromechanical library.			
Reference Boo	ks		
1. RS Muller	1. RS Muller, Howe, Senturia and Smith, "Micro-sensors", IEEE Press.		

	M. TECH FIRST YEAR			
Course Code	AMTVL0215	LT P	Credit	
Course Title	Nanoscale Devices: Modeling & Simulation	300	03	
Course Object	ctive:		I	
1	To introduce novel MOSFET devices and understan	d the		
	advantages of multi-gate devices			
2	To introduce the concepts of nanoscale MOS transistor	or and		
	their performance characteristics			
3	To study the various Nano-scaled MOS transistor circuits	5		
4 5	To study radiation effects in SOI MOSFETs			
5	To study digital circuits and impact of device performandigital circuits	ice on		
	Course Contents / Syllabus			
UNIT-I	MOSFET SCALING		8 hours	
	g, short channel effects - channel engineering - source/dra			
transistors - sing	c - copper interconnects - strain engineering, SOI MO le gate – double gate – triple gate – surround gate, quantum obility – thresholdvoltage–intersub-bandscattering, mult ck.	effects -	- volume	
UNIT-II	MOS ELECTROSTATICS		8 hours	
	atics – 1D – 2D MOS Electrostatics, MOSFET			
	Characteristics – CMOSTechnology – Ultimate limits, double gate MOS system – gate			
	emiconductor thickness effect – asymmetry effect – oxide t			
	electron tunnel current – two dimensional confinements, scattering –mobility.			
			101	
UNIT-III	SILICON NANOWIRE MOSFETS		10 hours	
	• MOSFETs – Evaluation of I-V characteristics – The I-V			
non- degenerate carrier statistics – The I-V characteristics for degenerate carrier statistics –				
Carbon nanotube – Band structure of carbon nanotube – Band structure of graphene – Physical structure of nanotube – Band structure of nanotube – Carbon nanotube FETs –				
-	Carbon nanotube MOSFETs – Schottky barrier carbon nanotube FETs – Electronic conduction			
	General model for ballistic nano transistors – MOSFETs w			
	cular transistors – Single electron charging – Single electron			
UNIT-IV	RADIATION EFFECTS IN SOI MOSFETS		6 hours	
	s in SOI MOSFETs, total ionizing dose effects – single-g			
	gle event effect, scaling effects.			
UNIT-V	DIGITAL CIRCUITS		8 hours	
	- impact of device performance on digital circuits – leaks			
	trade off - multi VT devices and circuits - SRAM design, analogcircuit design -			
transconductance - intrinsic gain - flicker noise - self heating -band gap voltage reference -				
operational amplifier – comparator designs, mixed signal – successive approximation				
DAC, RF circuit	8.			

Course Outcome: After successful completion of this course students will be able to		
CO 1	Explain the MOS devices used below 10nm and beyond with	
	an eye on the future	
CO 2	Explain the physics behind the operation of multi-gate systems.	
CO 3	To design circuits using nano-scaled MOS transistors with the	
	physical insight of their functional characteristics	
CO 4	Explain radiation effects in SOI MOSFETs	
CO 5	Explain and designdigital circuits and impact of device	
	performance on digital circuits	
Text books		
1. J P Coli	1. J P Colinge, "FINFETs and other multi-gate transistors", Springer – Series on	
integrate	integrated circuits and systems,2008	
2. Mark I	2. Mark Lundstrom, Jing Guo, "Nanoscale Transistors: Device Physics,	
Modelin	Modelingand Simulation", Springer,2006	
Reference bo	ooks	
1. M S Lundstorm, "Fundamentals of Carrier Transport", 2nd Ed., Cambridge University		
Press, Cambridge UK, 2000		

	M. TECH FIRST YEAR			
Course Code	AMTVL0216	LT P	Credit	
Course Title	Physical Design & Automation	300	03	
Course Object	ive:			
1	Students will know how to place the blocks and how to p	artition		
	the blocks while for designing the layout for IC.			
2	Students will be familiar to various kind of VLSI Automa	tion		
	Algorithms.			
3	Students will know the concepts of Physical Design Proce	SS		
4	such as Floor planning, Placement algorithms.			
4	Students will learn Global Routing and Detailed Routing			
5	algorithms.			
	Students will learn over the Cell Routing in detail.			
rre-requisites:	Basics of digital IC and data structures. Course Contents / Syllabus			
UNIT-I	LOGIC SYNTHESIS & VERIFICATION		8 hours	
	& Verification: Introduction combinational logic synthes	sis Bina		
•••	re models for High- level synthesis.	515, D 111a		
UNIT-II	VLSI AUTOMATION ALGORITHMS		8 hours	
	Algorithms: Partition: problem formulation, classifica	tion of		
	p migration algorithms, simulated annealing & evolutio			
algorithms.				
UNIT-III	PLACEMENT, FLOOR PLANNING & PIN ASSIGN	MENT	8 hours	
Placement, Floor	Planning & Pin assignment: problem-formulation, simulat	ion-based	d placement	
	r placement algorithms, constraint-based floor planni		or planning	
algorithms for mix	ked block & cell design. General & channel pin assignment.			
UNIT-IV	GLOBAL ROUTING & DETAILED ROUTING		8 hours	
Global Routing: Problem formulation, classification of global routing algorithms, Maze routing algorithm, line probe algorithm, Steiner Tree based algorithm, ILP based approaches.Detailed Routing: problem formulation, classification of routing algorithms, single layer routing algorithms, two-layer channel routing algorithms, three-layer channel routing algorithms, and switchbox routing algorithms.UNIT-VOVER THE CELL ROUTING & VIA MINIMIZATION8 hours			ayer routing	
	outing & via Minimization: two layers over the cell rou			
	•			
	unconstrained via minimization Compaction: problem formulation, one-dimensional compaction, two dimension-based Compaction, hierarchical compaction.			
Course Outcome: After successful completion of this course students will be able to				
CO 1	Know how to place the blocks and how to partition the	blocks		
~~ .	while for designing the layout for IC.			
CO 2	Explain VLSI Design Automation.			
CO 3	Explain the concepts of Physical Design Process such as planning, Placement and Routing.	s Floor		

(CO 4	AnalyzeGlobal Routing and Detailed Routing algorithms.	
(CO 5	Decompose large problem into pieces via minimization.	
Text	books		
1.	Naveed	Sherwani, "Algorithms for VLSI Physical Design Automation", Kluwer	
	Academic Publisher, Second edition.		
Refer	Reference Books		
1.	Christopl	nnMeinel&ThorstemTheobold, "Algorithm and Data Structures for VLS	
	Design", KAP 2002.		
2.	2. Rolf Drechsheler : "Evolutionary Algorithm for VLSI", second edition		
3.	• Trimburger," Introduction to CAD for VLSI", Kluwer Academic publisher, 2002.		

	M. TECH FIRST YEAR		
Course Code	AMTVL0217	LTF	Credit
Course Title	Embedded Microcontrollers	3 0 0	
Course Objec	tive:	I	
1	To provide the Basic knowledge of interfa	cing wit	h
	Embedded System.	0	
2	To analyse the process design of embedded system	stem.	
3	To realize the architecture of PIC 16F Microco Series.		
4	To familiar with the fundamentals of ARM Pro Cortex M3 & M4.	ocessor	
5	To apply the knowledge of ARM Instruction programming.	on Set fo	or
Pre-requisites	Digital System design, 8051 Microcontroller		
	Course Contents / Syllabus		
UNIT-I	TYPICAL EMBEDDED SYSTEMS		8 hours
Core of the embedded system, General purpose and domain specific processor, ASICs, PLDs, Commercial off the shelf Components (COTS), Memory: RAM, ROM, Memory according to the type of interface, Memory Shadowing, Memory selection for embedded system, Sensors and actuators, Introduction to Communication Interface (Onboard and			
External).	EMBEDDED SYSTEMS DESIGN PROCE	22	8 hours
•	m project development, Design issues and o cess, The Embedded Design Life Cycle, Selecti	0	•
	ware and Software partitioning), The Dev		
	be of target machine or its emulator and In-		
	ques, Introduction to BDM, JTAG, and Nexus.	Circuit	emulator), Special
UNIT-III	PIC 16F MICROCONTROLLER SERIES		8 hours
		it) DIC	
	PIC Microcontroller families (8/16 and 32 b		
	overview of architecture and peripherals, Pin diagram and Architecture of PIC16F84/PIC16F84A Microcontroller, Memory organization, configuration, memory		
	special function registers, parallel and serial		
-	of PIC16F84A (OSC Selection, RESET - Power	-	
_	Oscillator Start-up Timer (OST), Interrupts,		
	Protection, ID Locations, In-Circuit Serial		•
	prview of PIC 16F877/PIC 16F887A.	Tiografi	ining, interrupts).
	ARCHITECTURE OF ARM CORTEX M3		1 Q h anna
UNIT-IV	PROCESSORS		4 8 hours
Introduction to (Cortex-M3 and Cortex-M4 processors (Proces	sor archi	tecture, Instruction
	m, Memory system, Interrupt and exception su		
-	es, Registers, Memory System, features,		-
-	dianness, bit band operations, access permissi		• •
barriers, Low power design and features, low power application development, overview of			
exceptions and interrupts, exception types and interrupt management, vector table, exception			
1	NVIC register, SCB register and other special		· .
1 ,	43	0	1

-	ol, configuration control and auxiliary control registers.	
UNIT-V	INSTRUCTION SETOF CORTEX M3 AND M4 8 hours PROCESSORS	
Evolution of A	ARM ISA, Comparison of the instruction set in ARM Cortex-M Processor	
Unified Asser	nbly Language, Addressing modes, Instruction set, Program flow contra	
	tional branch, conditional execution, and function calls), Multiply accumula	
(MAC) instruc	ctions, Divide instructions, Memory barrier instructions, Exception-related	
instructions, S	leep mode-related instructions, Other functions, Introduction to Cortex-M	
processor sup	port for Enhanced DSP instructions, Writing C and Assembly language	
programs.		
Course Out	come: After successful completion of this course students will be able to	
CO 1	Explain the Basic knowledge of interfacing with	
	Embedded System.	
CO 2	Analyse the process design of embedded system.	
CO 3	Realize the architecture of PIC 16F Microcontroller	
	Series.	
CO 4	Familiar with the fundamentals of ARM Processor	
	Cortex M3 & M4.	
CO 5	Apply the knowledge of ARM Instruction Set for	
	programming.	
Text books		
1. Introdu	ction to Embedded Systems, A Cyber physical approach, Edward A. Lee ar	
Senjit A	A. Seshia.	
2. Embed	ded Systems Design: An Introduction to Processes, Tools, and Techniques, b	
Arnold	S. Berger, CMP Books.	
Reference B	Books	
1. Design	ing Embedded Systems with PIC Microcontrollers: Principles ar	
v	ations, 2nd Edition, Tim Wilmshurst, Elsevier Publication.	
	2. PIC Microcontroller and Embedded Systems Using Assembly and C for PIC 18 b	
Muham	mad Ali Mazidi, Rolin D. McKinlay and Danny Causey, Pearson Publication	
	finitive Guide to ARM Cortex M3 and Cortex-M4 Processors, Third Editio	
	Yiu, Elsevier Publication, 2015.	
*	Assembly Language Fundamentals and Techniques, William Hohl ar	
Christo	pher Hinds, CRC Press, 2015.	

	M. TECH FIRST YEAR		
Course Code	AMTVL0218 L T I	Credit	
Course Title	Real Time Operating System3 0 0	03	
Course Object	ive:		
1	To provide the concept of real time operating system.		
2	To analyse the task scheduling method & I/O system.		
3	To realize the firmware design process.		
4	To familiar with the different types of management system for RTOS.		
5	To explain the concept of RTX.		
Pre-requisites:	Digital System design, Microcontroller.		
	Course Contents / Syllabus		
UNIT-I	OPEN SOURCE RTOS	8 hours	
	Real-time concepts, Hard Real time and Soft Real-time,		
	Purpose OS & RTOS, Basic architecture of an RTOS, Schedul		
	nmunication, Performance Matric in scheduling model		
-	-	-	
	TOS environment, Memory management, File systems, I		
•	sadvantage of RTOS. POSIX standards, RTOS Issues – Sele	-	
	ystem, RTOS comparative study. Converting a normal Linux		
	mai basics. Overview of Open source RTOS for Embedded s	ystems (Free	
	Γ) and application development		
UNIT-II	Vx WORKS/ FREE RTOS	8 hours	
	ΓOS Scheduling and Task Management – Real time schedulin		
	Communication, Pipes, Semaphore, Message Queue, Signals		
Interrupts. I/O Sys	tems – General Architecture, Device Driver Studies, Driver M	lodule	
explanation, Imple	mentation of Device Driver for a peripheral.	•	
UNIT-III	EMBEDDED FIRMWARE DESIGN AND DEVELOPMENT	10 hours	
Embedded Firmwa	are Design Approaches, Super-loopbased approach, Embedd	ed Operating	
	oach, Programming in Embedded C, Integrated development		
	of IDEs for Embedded System Development.		
UNIT-IV	EMBEDDED SYSTEM DESIGN WITH FREE RTOS	6 hours	
Queue Manageme	ent, Characteristics of a Queue, Working with Large Da		
	ues within an Interrupt Service Routine, Critical Sections and	-	
the Scheduler, Resource Management, Memory Management.			
UNIT-V	RTX	8 hours	
	Y files RTX task and time management Simple Time Management		
	RTX structure, RTX files, RTX task and time management, Simple Time Management APIs, Task Priority Scheme in RTX, Inter-Task Communication, Event, Interrupt, Mutex,		
Semaphore, Mailboxes and Messages in RTX, RTX control functions, Architecture of			
CMSIS-RTOS.			
	Course Outcome: After successful completion of this course students will be able to		
CO 1	Explain the concept of real time operating system.		

(CO 2	Analyse the task scheduling method & I/O system.	
(CO 3	Realize the firmware design process.	
(CO 4	Familiar with the different types of management system for RTOS.	
(CO 5	Explain the concept of RTX.	
Text	books		
1.	Venkatesw Prentice Ha	aranSreekrishnan,"Essential Linux Device Drivers", Ist Kin all, 2008	dle edition,
2.	Jonathan W. Valvano, "Real-Time Operating Systems for ARM Cortex-M Microcontrollers" Jonathan Valvano; 4 edition		
Refer	ence Boo	ks	
1.	• •	perstein, "Writing Linux Device Drivers: A Guide with Ex n publishers, 2009	kercises", J.
2.	. Qing Li and Carolyn Yao,"Real Time Concepts for Embedded Systems" – Qing Li, Elsevier ISBN:1578201241 CMP Books © 2003		
3.	"Using the	FreeRTOS Real Time Kernel" From Free RTOS.	
4.	Sam Siewe	ert, "Real-Time Embedded Systems And Components".	

	M. TECH FIRST YEAR		
Course Code	AMTVL0219]	LT P	Credit
Course Title	4	300	03
Course Object	ive:		
1	Study the Architecture of Arm Cortex-M0 Processor.		
2	Describe the AMBA 3 AHB-Lite Bus Architecture	e,	
	VGA, GPIO and 7-Segment UART Peripheral		
3	Learn the Programming of SoC Using C Language.		
4	Compare ARM Cortex-A9 Processor with other		
	processor.		
5	Implement and compare an AXI UART and AXI-		
	Stream Peripheral		
	1. Basics of HDL (Verilog /VHDL)		
	2. Basics of Microcontroller Assembley language Progr	amming	
	Course Contents / Syllabus INTRODUCTION TO SYSTEM-ON-CHIP		
UNIT-I	DESIGN	Č	6 hours
Differences amon	g SoCs, CPUs and MCUs, Arm Cortex-M0 Processor A	rchitect	ure.
UNIT-II	PROGRAMMING AN SOC		8 hours
AMBA 3 AHB-I	ite Bus Architecture, AHB VGA Peripheral, AHB	UART	Peripheral,
Timer, GPIO and	d 7-Segment Peripherals, Interrupt Mechanisms, Pro	grammi	ng an SoC
Using C Language			
UNIT-III	ARM CORTEX-A9 PROCESSOR		8 hours
	Software Drivers, Arm Development Studio, ARMv7-	A/R ISA	Overview,
ARM Cortex-A9	AMBA AXI4		0 1
UNIT-IV		A 3/14 T ·	8 hours
	us Architecture, Design and Implementation of an ADDR Memory Controller	4X14-L1	te ^{rm} GPIO
* *	IMPLEMENTATION OF AN AXI UART AND		8 hours
	AXI-STREAM		0 110 u 1 5
Design and Imple	mentation of an AXI UART and AXI-Stream Peripheral	I, AXI4-	Stream and
VGA Peripheral, l	HDMI Input Peripheral, System Debugging.		
Course Outcon	ne:After completion of this course students will be a	ble to	
CO 1	Explain Arm Cortex-M0 Processor Architecture.		
CO 2	RecognizeAMBA 3 AHB-Lite Bus Architecture	e,	
	VGA, GPIO and 7-Segment UART Peripheral.	- ,	
CO 3	Program SoC Using C Language.		
CO 4	Explain ARM Cortex-A9 Processor.		
CO 5	Design and Implement an AXI UART and AXI-		
	Stream Peripheral.		
Text books	· · · ·	•	

- 1. ARM System-on-Chip Architecture by Steve B. Furber
- 2. ARM Assembly Language: Fundamentals and Techniques by William Hohl
- 3. The Definitive Guide to the ARM Cortex-M0 by Joseph Yiu

Reference Books

- 1. Computer System Design: System-On-Chip Michael J. Flynn and Wayne Luk, Wiely India.
- 2. Modern VLSI Design System on Chip Design Wayne Wolf, Prentice Hall,
- 3. Design of System on a Chip: Devices and Components, Ricardo Reis, Springer
- 4. System on Chip Verification Methodologies and Techniques: Prakash Rashinkar, Peter Paterson and Leena Singh L, Kluwer Academic Publishers

Link:	
Unit 1	https://www.youtube.com/watch?v=PRQXzjTrCJY
	https://www.youtube.com/watch?v=HNbeVvfFKsQ
Unit 2	https://www.youtube.com/watch?v=j2NI4AXRs1Uhttps://www.youtube.com/watch?v=
	4VRtujwa_b8&list=PL90187D2B8F5AC28F&index=5
Unit 3	https://www.youtube.com/watch?v=4VRtujwa_b8
Unit 4	https://www.youtube.com/watch?v=mYP5SxDEjrM
	https://www.youtube.com/watch?v=QQY-h0HGHnI
	https://www.youtube.com/watch?v=tEvtb-
	mdJ4s&list=PL90187D2B8F5AC28F&index=16
Unit 5	https://www.youtube.com/watch?v=nbWWMPPC8aE
	https://www.youtube.com/watch?v=MANrmky5DfE